



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of : **Confirmation No. 8121**
Kazuyuki NITTA et al. : **Docket No. 2001_1143A**
Serial No. 09/928,430 : **Group Art Unit 1752**
Filed August 14, 2001 : **Examiner S. Lee**

5/2

**POSITIVE-WORKING PHOTORESIST
COMPOSITION AND RESIST
PATTERNING METHOD USING SAME**

THE COMMISSIONER IS AUTHORIZED
TO CHARGE ANY DEFICIENCY IN THE
FEES FOR THIS PAPER TO DEPOSIT
ACCOUNT NO. 23-0975

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RESPONSE

Assistant Commissioner for Patents,
Washington, D.C.

Sir:

In response to the Official Action dated November 6, 2002, please amend the present application as follows:

IN THE CLAIMS:

Please cancel claims 2-4 without prejudice to the subject matter thereof.

Please amend claims 1 and 11 as follows:

1. (Amended) A positive-working photoresist composition which comprises, as a uniform solution in an organic solvent:
- (A) 100 parts by weight of a hydroxystyrene-based polymer which is a combination of:
 - (A1) a first polyhydroxystyrene resin having phenolic hydroxyl groups a part of which are substituted for the hydrogen atoms thereof by acid-dissociable alkoxyalkyl groups; and

S. Lee
A